TRANSMITTAL OF INFORMATION DISCLOSURE STATEMENT (Under 37 CFR 1.97(b) or 1.97(c))						Docket No. SETI-0002DIV		
In Re Application Of:								
Khan et al.		HOV 0 3						
Serial No.	rial No. Filing Date Examiner Group Art Unit							
10/647,714	8/25/2003			Unknown		Unknown		
Title: METAL OXIDE S	SEMICONDUCTOR HET	EROSTRUC	CTURE	FIELD EFFECT	TRAN	SISTOR		
	Address to: Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450							
		37 CFR '	1.97(b)					
1. The Information Disclosure Statement submitted herewith is being filed within three months of the filing of a national application other than a continued prosecution application under 37 CFR 1.53(d); within three months of the date of entry of the national stage as set forth in 37 CFR 1.491 in an international application; before the mailing of a first Office Action on the merits, or before the mailing of a first Office Action after the filing of a request for continued examination under 37 CFR 1.114.								
		37 CFR	1.97(c)					
2. ☐ The Information Disclosure Statement submitted herewith is being filed after the period specified in 37 CFR 1.97(b), provided that the Information Disclosure Statement is filed before the mailing date of a Final Action under 37 CFR 1.113, a Notice of Allowance under 37 CFR 1.311, or an Action that otherwise closes prosecution in the application, and is accompanied by one of:								
☐ the statement specified in 37 CFR 1.97(e);								
OR								
the fee set forth in 37 CFR 1.17(p).								

	OSURE STATEMENT	Docket No. SETI-0002DIV							
In Re Application:	<u></u>	To To							
Khan et al.	VON	0 3 2003							
Serial No.	Filing Date 8/25/2003	Examiner	Group Art Unit						
10/647,714	8/25/2003	Unknown	Unknown						
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	Payment of Fee								
	•	elects to pay the fee set forth in 37 CFF	R 1.17(p))						
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	Signature	Signature of Person	Mailing Correspondence						
Toursday Drinted A	Contract Continue	Dorothea Rubbone							
	Name of Person Signing Certificate	Typed or Printed Name of P	Person Mailing Certificate						
201	ay only be used if paying by Signature	Dated: October 30, 2003							
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		"Optoelectronic GaN-b	ased Field Effect	Transistors," M. S. Shur et al., SPI	E, Vol. 2397, p	pp. 294-303, F	eb. 7, 1995.	
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	"GaN - AlxGa1-xN Het Insulator Semiconducto Proceedings Vol . 281 (erostructures Depos r Field Effect Trans 1993), pp.769-774.	ition by Low Pressure Metalorg istor (MISFET) Devices," M. Ki	anic Chemical nan et al., Ma	Vapor Deposit terial Research	tion For Metal Society Symposium		
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INFORM	* A TOOM DISCOLUSE COT A TION	SETI-006	09/966559
HAL OWA	AATION DISCLOSURE CITATION (Use several sheets if necessary)	Applicant(s) Khan et al.	
		Filing Date 9/27/2001	Group Art Unit 2818
*EXAMINER	OTHER DOCUMENTS (Including Author, Titl	le, Date, Pertinent Pages, Etc.)	
PE	Ren, F. et al., "Effect f temperature on Ga2O3(Gd	12O3)/GaN metal-oxide-semiconducto	or field-effect transistors," Applied
MIN D 3 TOTAL	Physics Letters, vol. 73, No. 26, 28 December 1998,	s, pp. 3893-3895.	
TRANSTRANSPARENTS	Gaska, R. et al., "Electron mobility in modulation-d 2, 11 January 1999, pp. 287-289.	loped AlGaN-GaN heterostructures,"	Applied Physics Letters, Vol. 74, No.
	Khan, M.A. et al., "Current/voltage characteristic of transistors at high drain bias," Electronics Letters,	collapse in AlGaN/GaN heterostructur Vol. 30, No. 25, 8 December 1994, pp	re insulated gate field effect 2175-2176.
	Carrano, J.C. et al., "Very low dark current metal- GaN epitaxial layers," Applied Physics Letters, Vol	semiconductor-metal ultraviolet phot l. 70, No. 15, 14 April 1997, pp. 1992-	odetectors fabricated on single-crystal 1994.
	Chen, Q. et al., "Schottky barrier detectors on GaN No. 17, 28 April 1997, pp. 2277-2279.	for visible-blind ultraviolet detection	ı," Applied Physics Letters, Vol. 70,
	Khan, M.A. et al., "AlGaN/GaN metal-oxide-semico Applied Physics Letters, Vol. 77, No. 9, 28 August 2	onductor heterostructure field-effect t (000, pp. 1339-1341.	transistors on SiC substrates,"
	Shur, M.S. and Khan, M.A., "GaN and AlGaN Devi Science Publishers, Series Optoelectronic Properties II, pp. 47-92, S. Pearton, Editor (1999).	ices: Field Effect Transistors and Pho s of Semiconductors and Superlattices	otodetectors," Gordon and Breach s, Vol. 7 GaN and Related Materials
	Shur, M.S. and Khan, M.A., "Wide Band Gap Semi 23rd Int. Symp. Compound Semiconductors, St. Pet	iconductors. Good Results and Great tersburg, Russia, 23-27 September 19	t Expectations," Paper presented at 96, pp. 25-31.
	Khan, M.A. et al., "AlGaN/GaN Metal Oxide Semic Letters, Vol. 21, No. 2, February 2000, pp. 63-65.	conductor Heterostructure Field Effec	ct Transistor," IEEE Electron Device
EXAMINER		DATE CONSIDERED	
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not considered. Include copy of this form with next communication to applicant.